Institute of Radiation Physics Radiation Source ELBE

Status report of ELBE and GaN BETH kickoff meeting, Siegen

Jana Schaber Helmholtz Zentrum Dresden-Rossendorf j.schaber@hzdr.de www.hzdr.de



Performance of the SRF Gun

Advantages of SRF Gun II: • continuous wave operation (CW) higher bunch charge lower transverse emittance short pulses to high-field laboratory infrared FELs **DT** neutron nToF neutrons ion wakefield optical lat . max. 0.1-10 MeV 3 - 230 um generator, 14 MeV acceleration laboratory free-electron la $0.1 - 3 \, \text{mm}$ 1 mA, 40 MeV SC-CW-LINAC THz facility accelerator hall 1000-CBS X-Ray, 12 keV - 20 keV SRF gun nuclear apectros-DRACO electron wakefeld accelerator electronics radiation physics X-ray laboratory positron ladicidatory (150 TW LASER) 10-100 keV X-Ray, positrons (MePS) 0...18 MeV 30 MeV single bunch 0.2 - 30 keV bremsstrahlung, PENELOPE positrons (GiPS) and single electrons (1.5 PW LASER) extension (2010-2014)

• working hours for THz radiation production at ELBE, all TELBE shifts in 2019 (101 shifts a 12 h)



Mg Photocathode

Mg cathodes work routinely in ELBE SRF gun at HZDR

- bulk Mg plugs, polished and chem. cleaned
- UV laser cleaning (drive laser)
- best QE 0.3 % ... 0.5 %
- low risk of cavity contamination
- extremely long life time in 10⁻⁹ mbar vacuum
- cleaning can be several times repeated







Build-up and commissioning of GaN chamber





Software program

GaN Photocathode Research



Build-up and commissioning of GaN chamber







Outgassing of Cs-dispenser



- Current to Cs: from 2 to 4.3 A
- 4 h at 2.7 A
- Kept at 1 A during outgassing/heating with halogen lamp

DRESDEN concept

Outgassing of halogen lamp & heating sample





→ Reached T on sample: 610°C
 → Heating time: 15 min
 → Stopped because of too bad vacuum (~ 1E-6mbar)



First activation- process





- reached ~0.58 %
 → no loss during the fire
 - \rightarrow no loss during the first hours
- On 2nd day after activation: oxygen in chamber
 - \rightarrow destroyed cathode





Cleaning of GaN on sapphire

GaN: reference



Crystal growth after cleaning ?!?! \rightarrow Avoid air exposure+ use Glovebox & sealed bags



Conclusion

- Charaterization and comparison of commercial available GaN wafer
 - → GaN on sapphire, Si, SiC (different substrates)
 - \rightarrow <u>AFM, XPS</u>, EDX, SEM, RBS
- Connection from activation chamber to XPS chamber \rightarrow 1st quarter 2020
- Activation of GaN wafer with Cs and characterization of activated GaN

 → further activations and improvement
- Comparision to GaAs & selfmade GaN (Uni Siegen)
- If sucessfully: test in SRF Gun II as a photocathode for high brightness beam



Thank you for your attention!

Thanks to the ELBE team

J.Teichert, A. Arnold, P. Zwartek, P. Lu, S. Ma, P. Murcek, H. Vennekate, R. Xiang, P. Evtushenko, M. Freitag, M. Justus, M. Kuntzsch, U. Lehnert, P. Michel, A. Ryzhov, C. Schneider, R. Steinbrück, K. Zenker, and our co-workers

- P. Kneisel, G. Ciovati JLAB, Newport News, USA
- I. Will MBI, Berlin, Germany
- T. Kamps, J. Kühn, M. Schenck, M. Schmeißer, G. Klemz,
- J. Voelker, HZB, Berlin, Germany
- J. Sekutowicz, E. Vogel, F. Stephan, H. Qian, DESY, Germany
- K. Aulenbacher, JGU, Mainz, Germany
- M. Vogel, M. Schuhmacher, X. Jiang, Uni Siegen, Germany
- R. Nietubyć NCBJ, Świerk/Otwock, Poland
- U. van Rienen, E. T. Tulu, Uni Rostock, Germany





